

AMENDMENTS TO THE CLAIMS

Claim 1 (currently amended): Enamel composition for producing reflecting dielectric layers in plasma display panels, comprising as layer forming ~~constituants~~ constituents 70 to 97% by weight of a glass frit composition having a softening temperature of less than 600°C and 3 to 30% by weight of a particulate whitening material, characterized in that the whitening material consists of at least 50% by wt. of one or more thermally deactivated white pigments, 0 to 50% by wt. of other white pigments and 0 to 20% by wt. of one or more opacifiers and whereby the one or more thermally deactivated white pigments have been made by a process comprising heating of at least one white pigment in the absence or presence of a glass frit having a softening temperature of less than 600°C at a temperature of 600 to 1000°C for θ , ~~+~~ 0.1 to 10 hours.

Claim 2 (currently amended): Enamel composition according to claim 1, characterized in that the layer forming ~~constituants~~ constituents comprise essentially 70 to 90% by wt. of a glass frit composition having a softening temperature of less than 560°C, 10 to 25% by wt. of a deactivated white pigment which can be coated with a glass frit and 0 to 5% by wt. of an opacifying agent.

Claim 3 (currently amended): Enamel according to claim 1, characterized in that the ~~deactivated~~ deactivated white pigment is made from titanium dioxide.

Claim 4 (currently amended): Enamel composition according to claim 1, characterized in that the deactivated white pigment is made by a process, comprising transferring of a white pigment into briquettes, heating said briquettes at 600 to 1000°C for θ , ~~+~~ 0.3 to 3 hours and crushing the so treated briquettes.

Claim 5 (currently amended): Enamel composition according to claim 1, ~~characterized~~
~~characterized on in~~ that the deactivation of the white pigment is ~~made~~ carried out by a process
comprising (i) preparing ~~of~~ a homogeneous powder mixture of at least 50% by wt. of a glass frit
having a softening temperature of less than 600°C, (ii) transferring the mixture into briquettes,
(iii) treating said briquettes at 600 to 800°C for ~~0.3~~ 0.1 to 3 hours and (iv) crushing the thermally
treated briquettes.

Claim 6 (previously presented): Enamel composition according to claim 1, characterized
in that a glass layer made from said enamel composition by coating and firing has a breakdown
voltage of greater than 400 V/25 µm.

Claim 7 (currently amended): Enamel composition according to claim 1, characterized in
that the glass frit composition is based on a lead borosilicate glass, essentially containing (wt.-%)
PbO from 55 to 90%, B₂O₃ from 6 to 35%, SiO₂ from 6 to 40%, CaO and BaO from ~~0.1~~ 0.1 to
2% and Na₂O and K₂O from ~~0.1~~ 0.1 to 2% and having a softening temperature T_s of 390 to
520°C and a thermal expansion coefficient of (60 to 90) x 10⁻⁷ K⁻¹.

Claim 8 (previously presented): Enamel composition according to claim 1, characterized
in that the layer forming constituents are dispersed in a liquid or thermoplastic medium.

Claim 9 (currently amended): Enamel composition according to claim 8, characterized in
that it consists essentially ~~consists~~ of 60 to 80% by wt. of layer forming ~~constituants~~ constituents
and 40 to 20% by wt. of a liquid printing medium containing a polymer binder and at least a
solvent system.

Claims 10 - 12 (canceled)

Claim 13 (currently amended): Process for ~~enamelling~~ enameling a glass substrate, comprising coating the substrate with an enamel composition consisting essentially of glass layer forming constituents ~~dispered~~ dispersed in a liquid or thermoplastic medium and firing the coated substrate ~~on~~ at a temperature in the range of 600 to 680°C, characterized in that ~~an~~ the enamel composition ~~as to~~ of claim 8 is used.

Claim 14 (previously presented): Process according to claim 13, characterized in that the coating is performed by screen printing followed by drying.

Claim 15 (currently amended): Plasma display panels comprising a first array of electrodes embedded in a first dielectric layer on a rear substrate, a second array of electrodes embedded in a second dielectric layer on a cover substrate and a pattern of a barrier for defining discharge spaces in between, characterized in that the first dielectric layer on the rear substrate is a reflecting essentially white enamel made by coating the substrate with an enamel composition according to claim 1 and firing at a temperature in the range of 600 to 680°C.

Claim 16 (currently amended): Plasma display panels comprising a first array of electrodes embedded in a first dielectric layer on a rear substrate, a second array of electrodes embedded in a second dielectric layer on a cover substrate and a pattern of a barrier for defining discharge spaces in between, characterized in that the first dielectric layer on the rear substrate is a reflecting essentially white enamel made by coating the substrate with an enamel composition according to claim 2 and firing at a temperature in the range of 600 to 680°C.

Claim 17 (currently amended): Plasma display panels comprising a first array of electrodes embedded in a first dielectric layer on a rear substrate, a second array of electrodes embedded in a second dielectric layer on a cover substrate and a pattern of a barrier for defining

discharge spaces in between, characterized in that the first dielectric layer on the rear substrate is a reflecting essentially white enamel made by coating the substrate with an enamel composition according to claim 3 and firing and firing at a temperature in the range of 600 to 680°C.

Claim 18 (currently amended): Plasma display panels comprising a first array of electrodes embedded in a first dielectric layer on a rear substrate, a second array of electrodes embedded in a second dielectric layer on a cover substrate and a pattern of a barrier for defining discharge spaces in between, characterized in that the first dielectric layer on the rear substrate is a reflecting essentially white enamel made by coating the substrate with an enamel composition according to claim 7 and firing at a temperature in the range of 600 to 680°C.

Claim 19 (currently amended): Plasma display panels comprising a first array of electrodes embedded in a first dielectric layer on a rear substrate, a second array of electrodes embedded in a second dielectric layer on a cover substrate and a pattern of a barrier for defining discharge spaces in between, characterized in that the first dielectric layer on the rear substrate is a reflecting essentially white enamel made by coating the substrate with an enamel composition according to claim 8 and firing at a temperature in the range of 600 to 680°C.

Claim 20 (currently amended): Plasma display panels comprising a first array of electrodes embedded in a first dielectric layer on a rear substrate, a second array of electrodes embedded in a second dielectric layer on a cover substrate and a pattern of a barrier for defining discharge spaces in between, characterized in that the first dielectric layer on the rear substrate is a reflecting essentially white enamel made by coating the substrate with an enamel composition according to claim 9 and firing at a temperature in the range of 600 to 680°C.